FIG. 1A

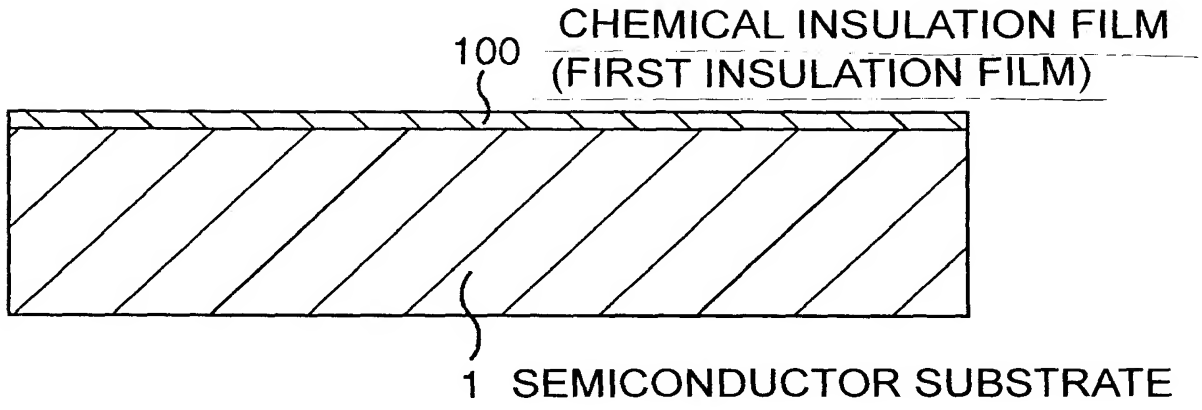

CHEMICAL INSULATION FILM
(FIRST INSULATION FILM)
100
1 SEMICONDUCTOR SUBSTRATE

FIG. 1B

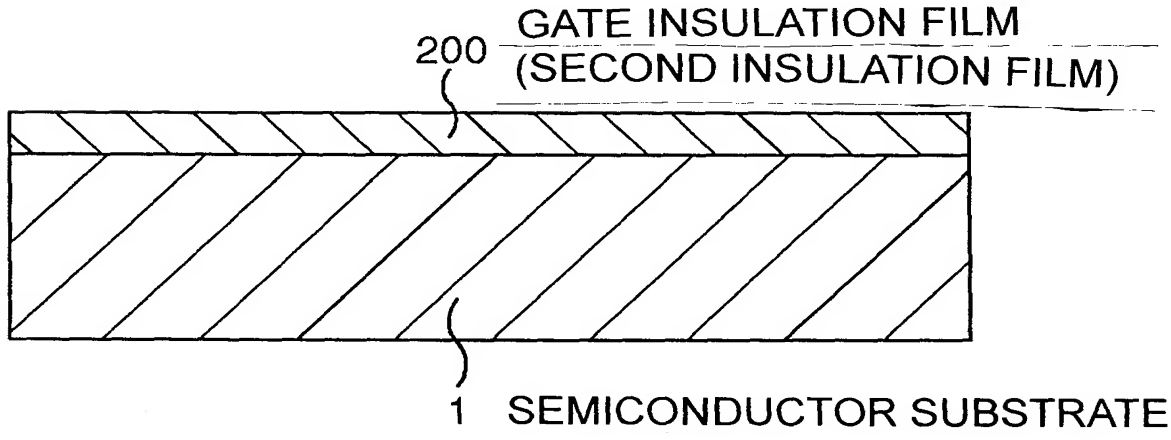

GATE INSULATION FILM
(SECOND INSULATION FILM)
200
1 SEMICONDUCTOR SUBSTRATE

FIG. 2A

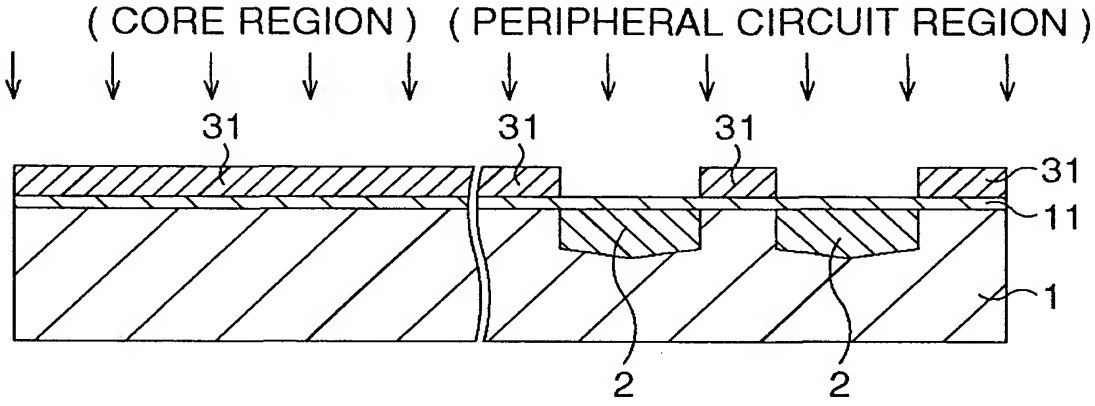


FIG. 2B

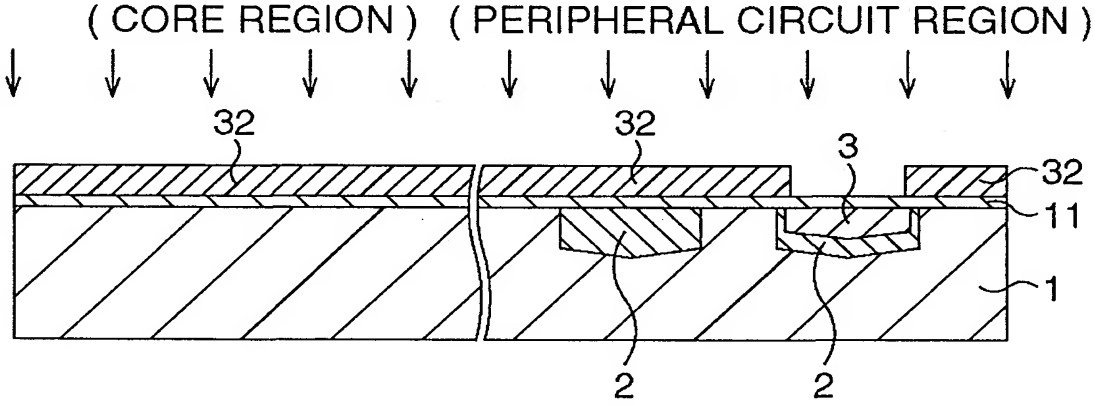


FIG. 2C

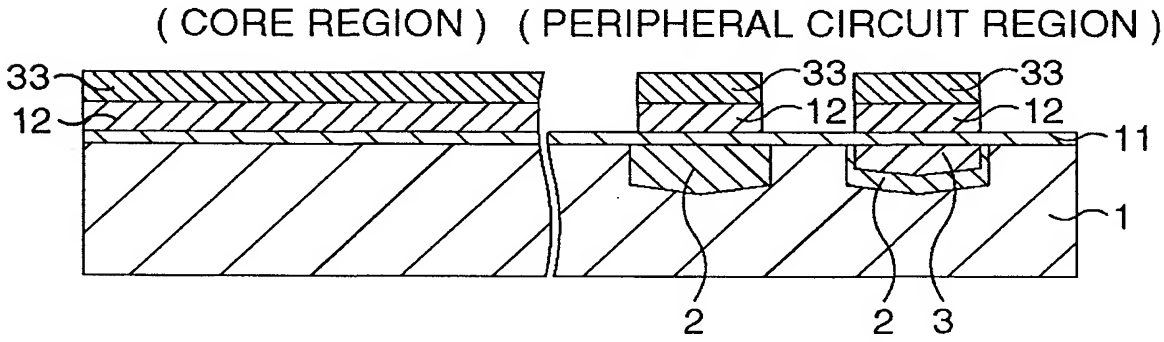


FIG. 2D

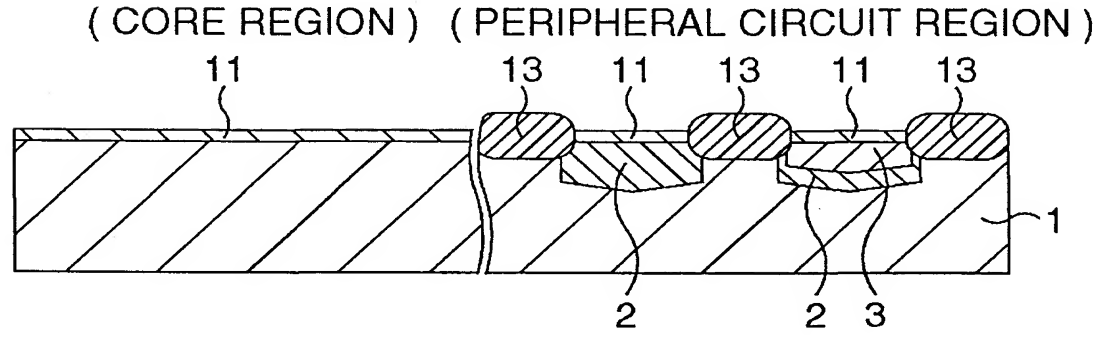


FIG. 3A

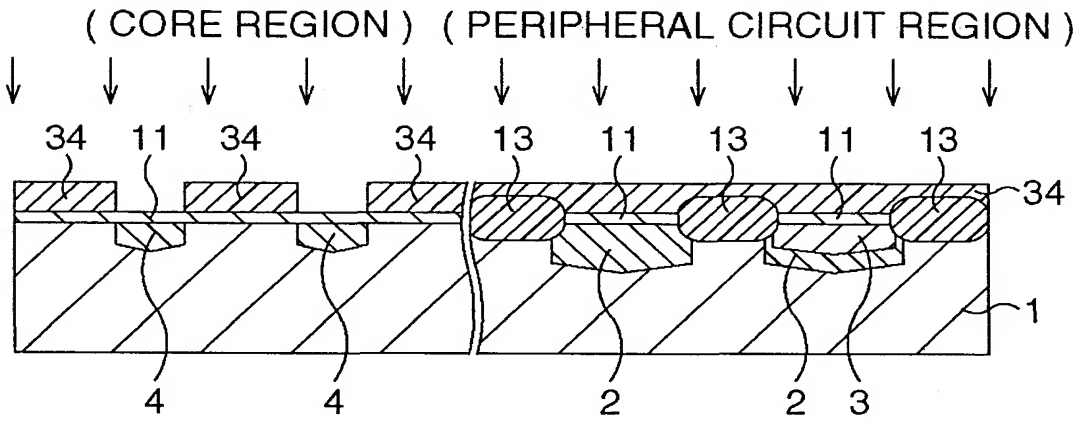


FIG. 3B

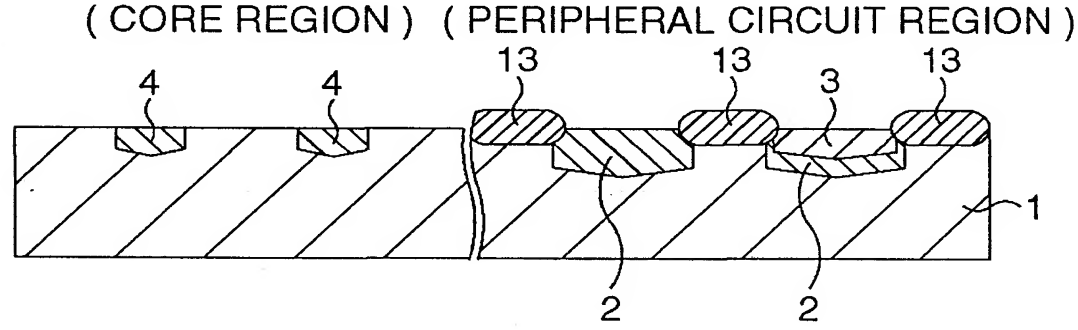


FIG. 3C

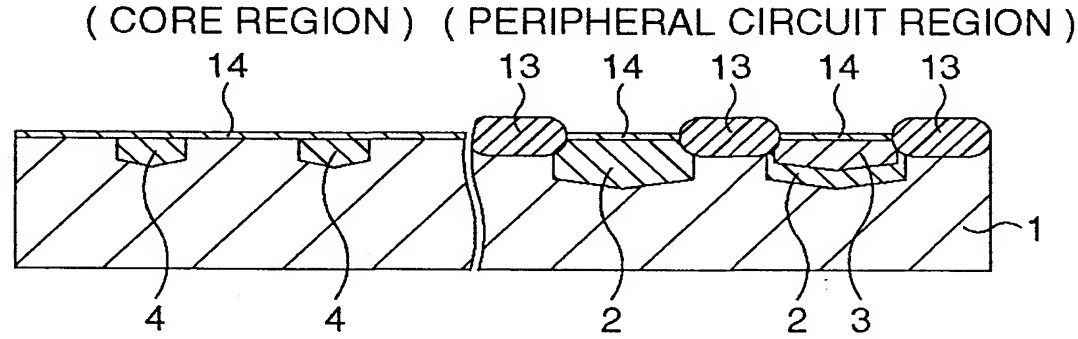


FIG. 3D

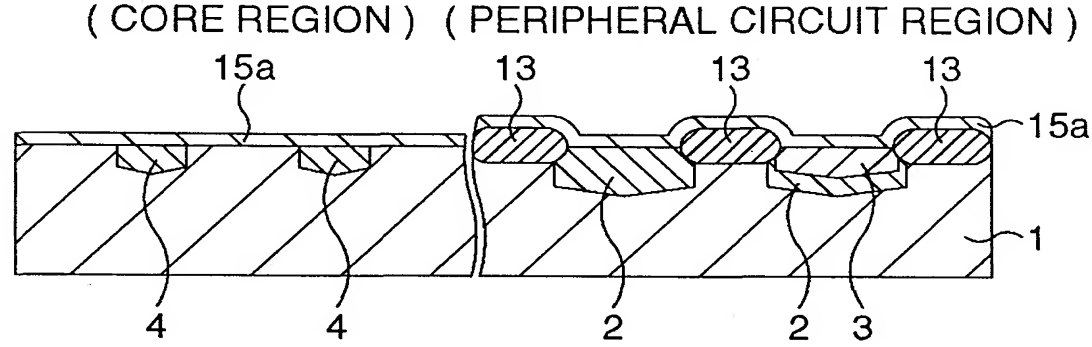


FIG. 4A

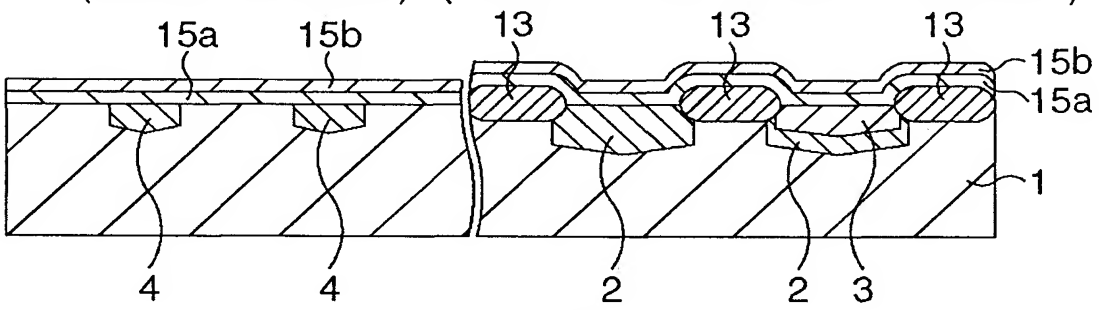


FIG. 4B

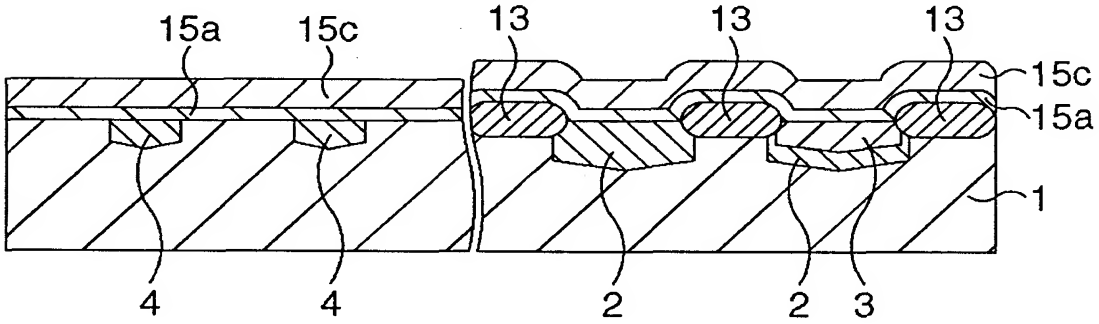


FIG. 4C

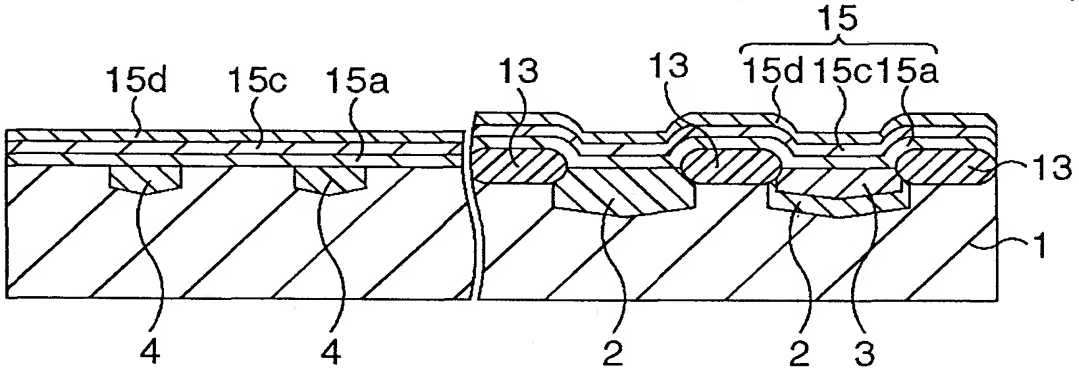


FIG. 4D

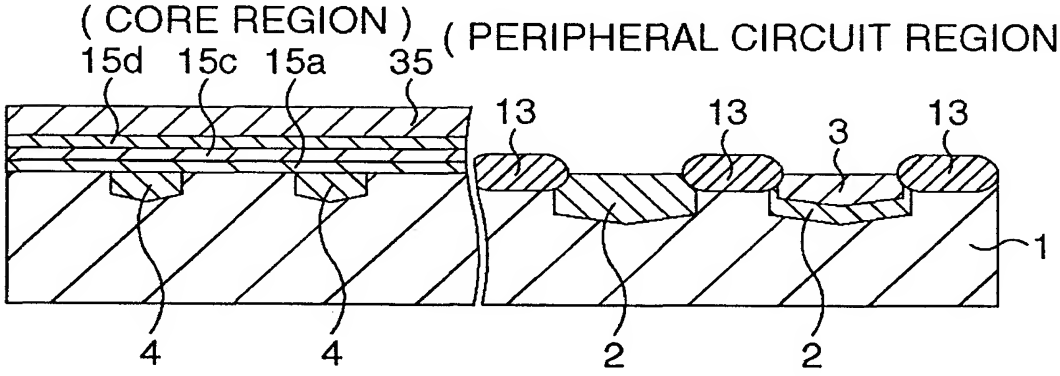


FIG. 5A

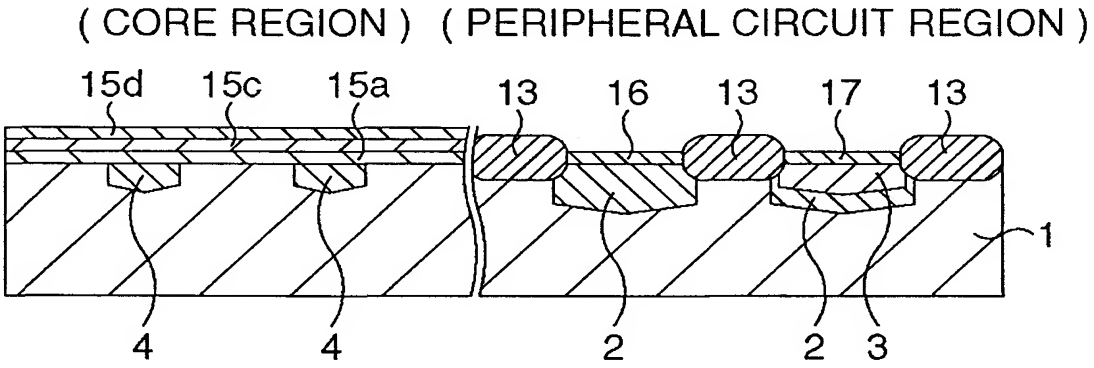


FIG. 5B

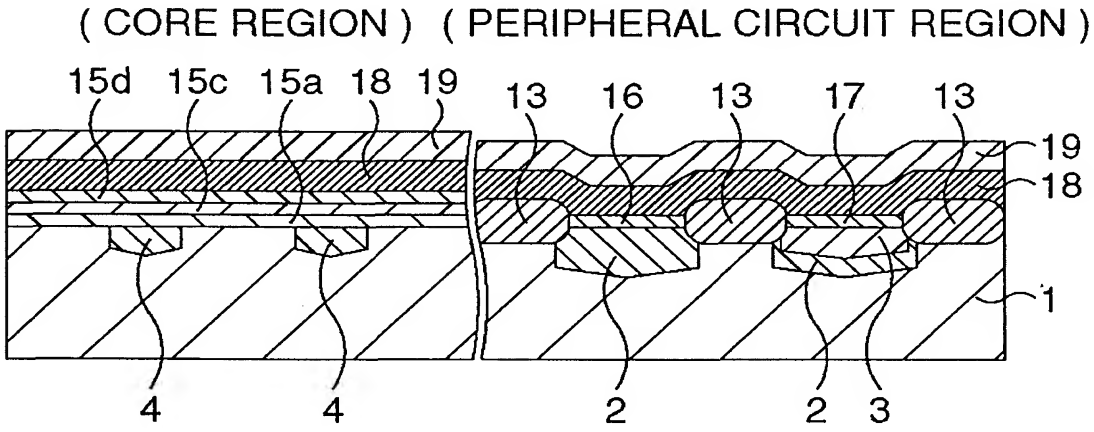


FIG. 5C

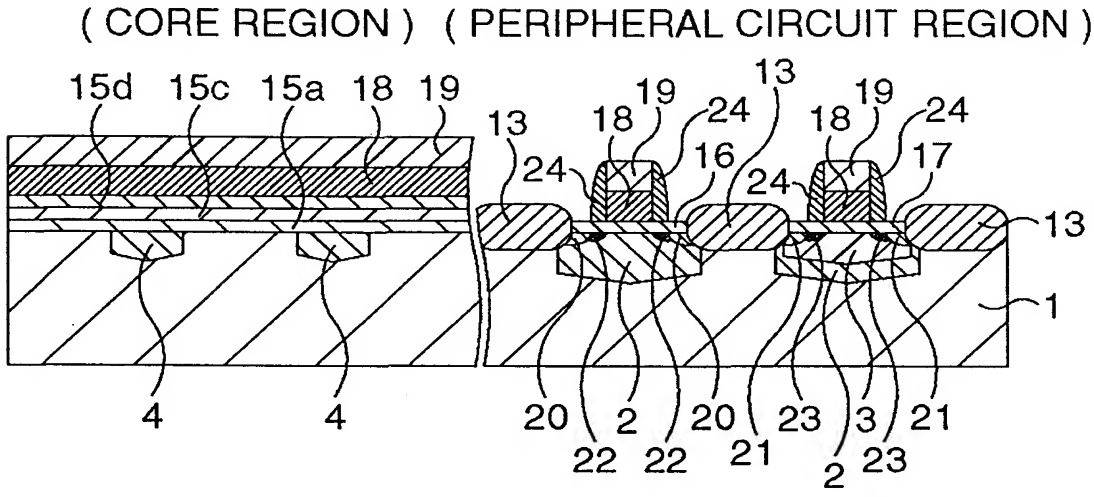


FIG. 6A

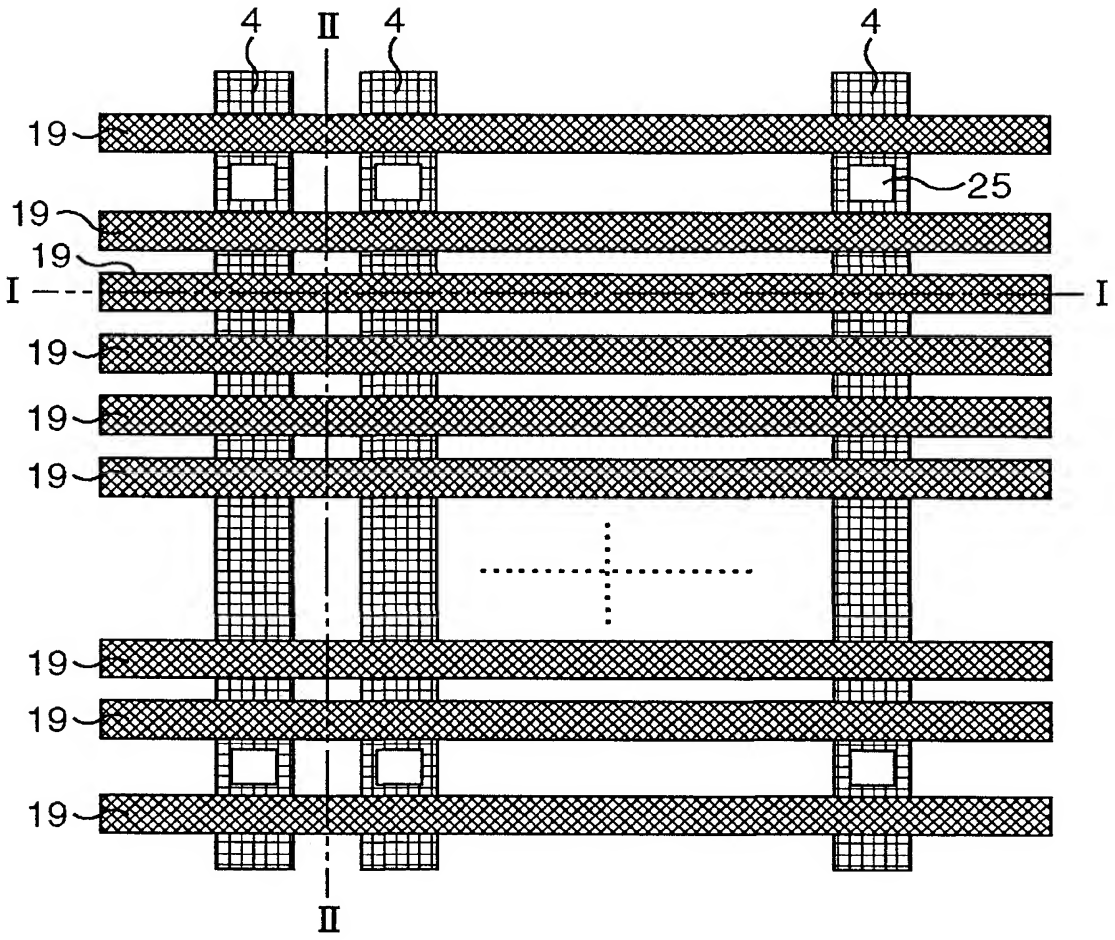

4
II
4
4
19
25
19
19
I
I
19
19
19
19
19
19
II

FIG. 6B

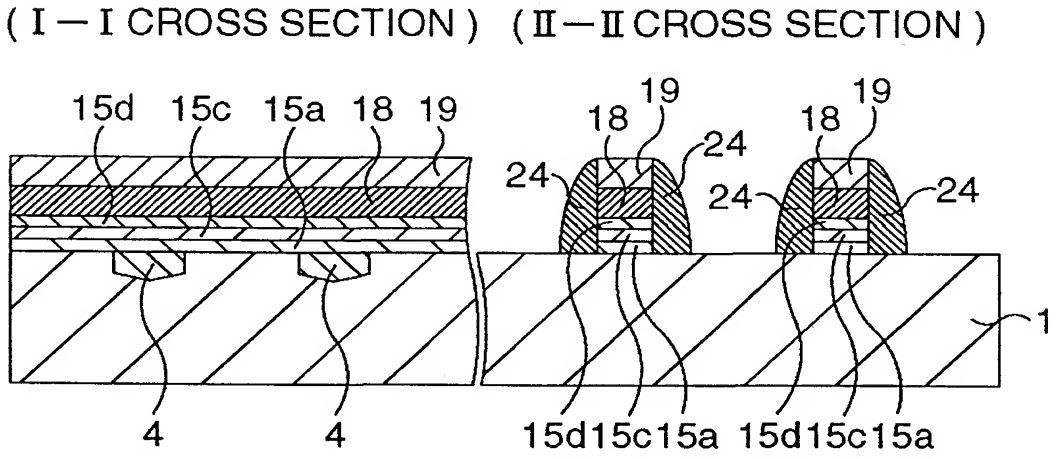

(I — I CROSS SECTION)
(II — II CROSS SECTION)
15d
15c
15a
18
19
18
19
18
19
24
24
24
24
1
4
4
15d15c15a
15d15c15a

FIG. 7

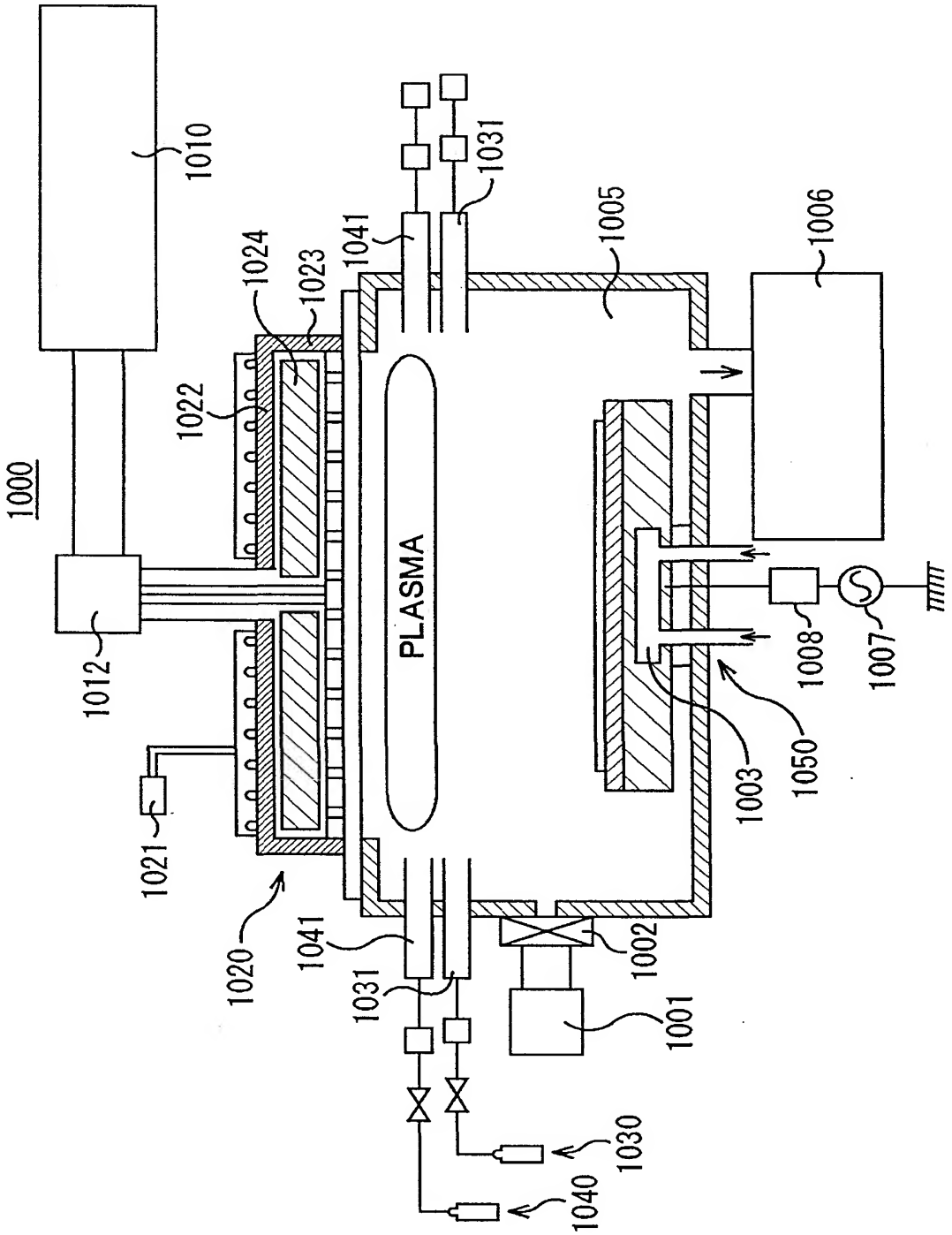
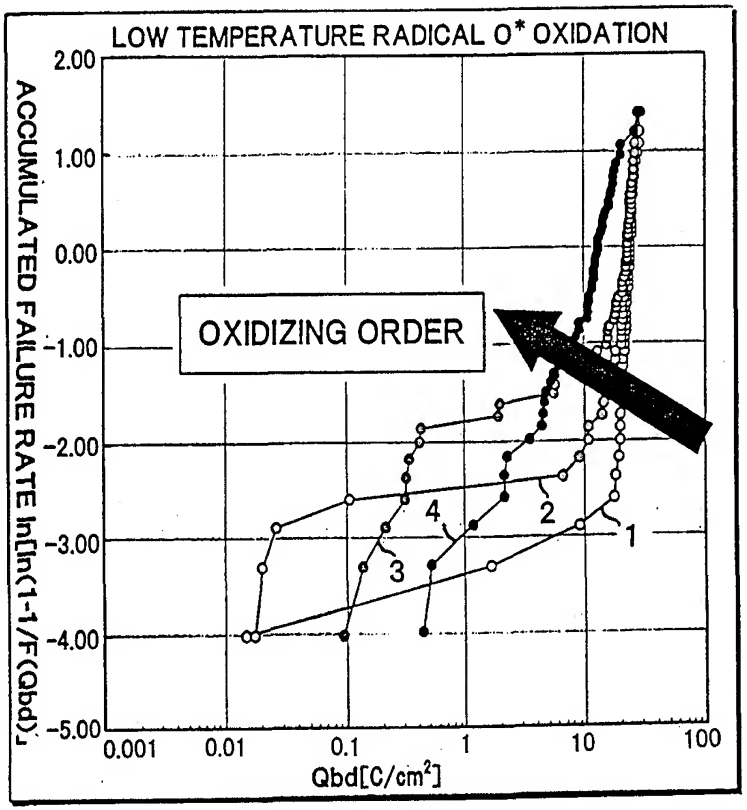
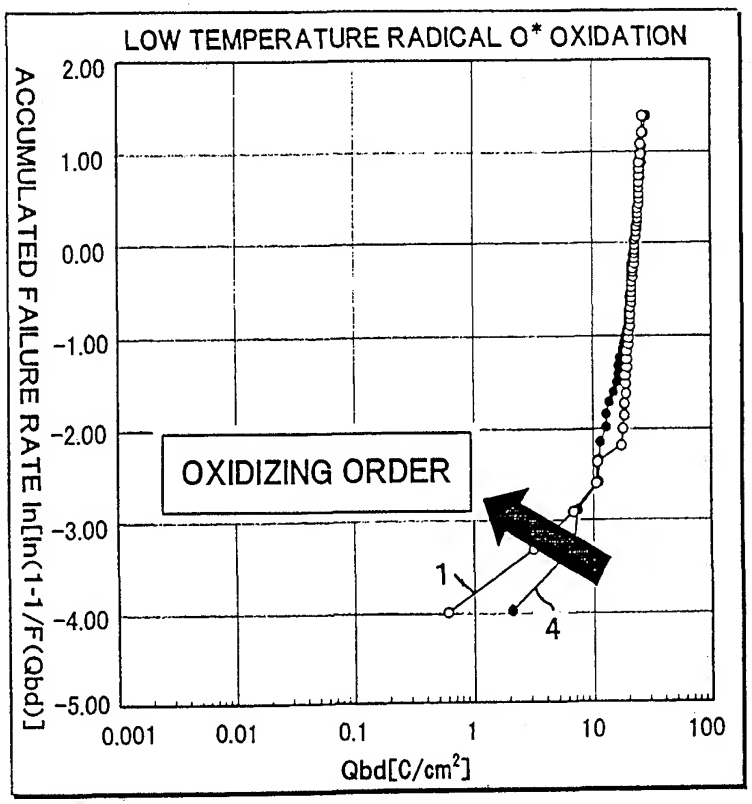

1000
1010
1012
1020
1021
1022
1023
1024
1031
1041
1005
1006
1008
1007
1003
1050
1002
1001
1030
1040
PLASMA

FIG. 8A



HCL CHEMICAL OXIDE FILM

FIG. 8B



HNO3 CHEMICAL OXIDE FILM